CLAIMS

1. Composition comprising ethanesulfonic acid or 1-propanesulfonic acid ~~and a proton acceptor~~, for use in removing biofilm and necrotic or infected tissues from a skin lesion~~, wherein said proton acceptor is selected from the group consisting of: dimethyl sulfoxide, silicon dioxide, tetraethoxysilane, and mixtures thereof~~.

2. Composition for the use according to claim 1, wherein said ethanesulfonic acid is ethanesulfonic acid 97% and said 1-propanesulfonic acid is 1-propanesulfonic acid 98%.

3. Composition for the use according to claim 1, or 2, further comprising a proton acceptor.

4. Composition for the use according to claim 3, wherein said proton acceptor is selected from the group consisting of: dimethyl sulfoxide, silicon dioxide, tetraethoxysilane, and mixtures thereof.

~~3~~5. Composition for the use according to any one of claim 1 or ~~2~~4, prepared in the form of a gel.

~~4~~6. Composition for the use according to ~~any one of claims 1 to 3~~claim 4, or 5, having the following formulation:

Ethanesulfonic acid	70-90% by weight
Dimethyl sulfoxide	5-20% by weight
Silicon dioxide	1-8% by weight
Tetraethoxysilane	0.05-2% by weight

~~5~~7. Composition for the use according to ~~any one of claims 1 to 3~~claim 4, or 5, having the following formulation:

1-propanesulfonic acid	70-90% by weight
Dimethyl sulfoxide	5-20% by weight
Silicon dioxide	1-8% by weight
Tetraethoxysilane	0.05-2% by weight

~~6~~8. Composition for the use according to any one of claims 1 to ~~5~~7, wherein said use comprises removing said composition from said skin lesion after a contact time of a few tens of seconds has elapsed.

~~7~~9. ~~—~~Composition for the use according to any one of claims 1 to ~~6~~8, wherein said skin lesion is a chronic cutaneous ulcer.